

FIG. 1

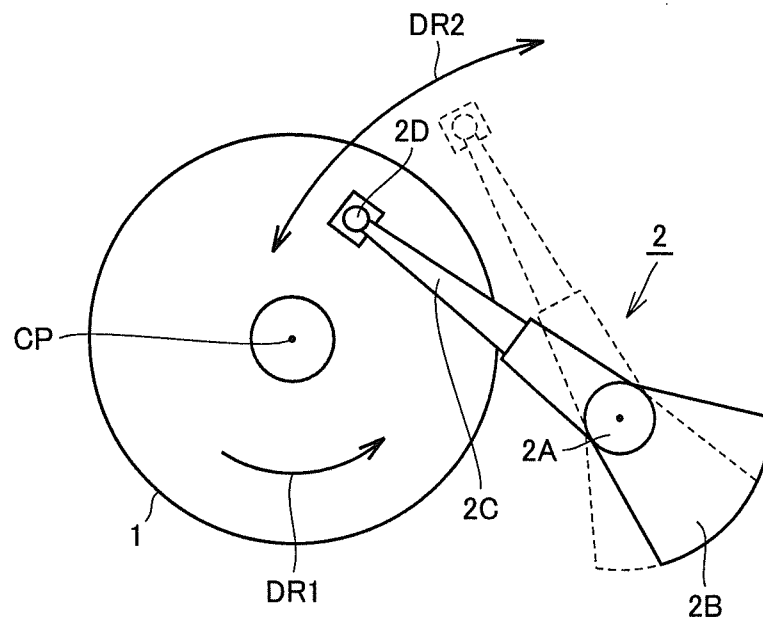


FIG.2

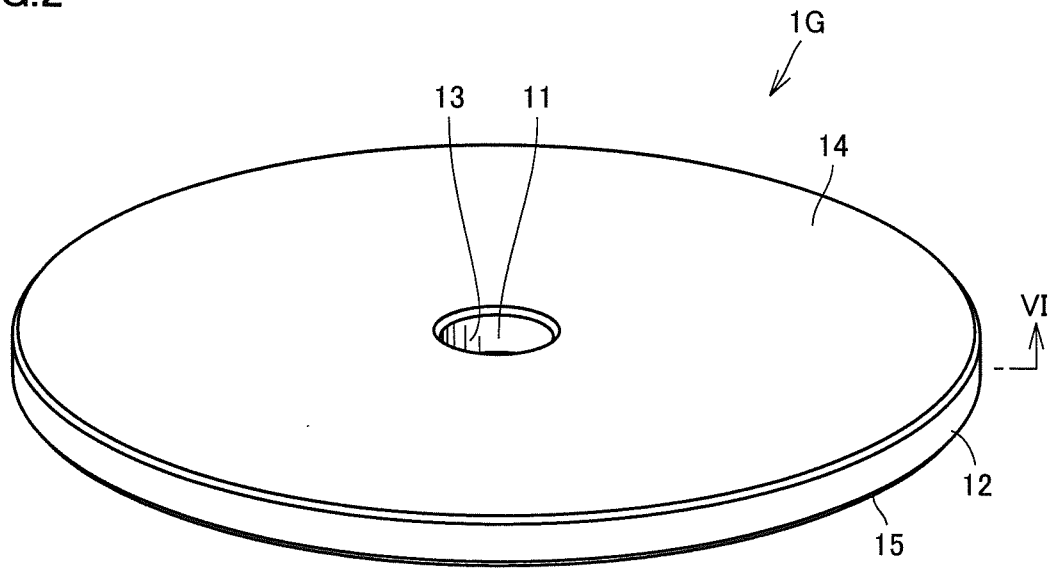


FIG.3

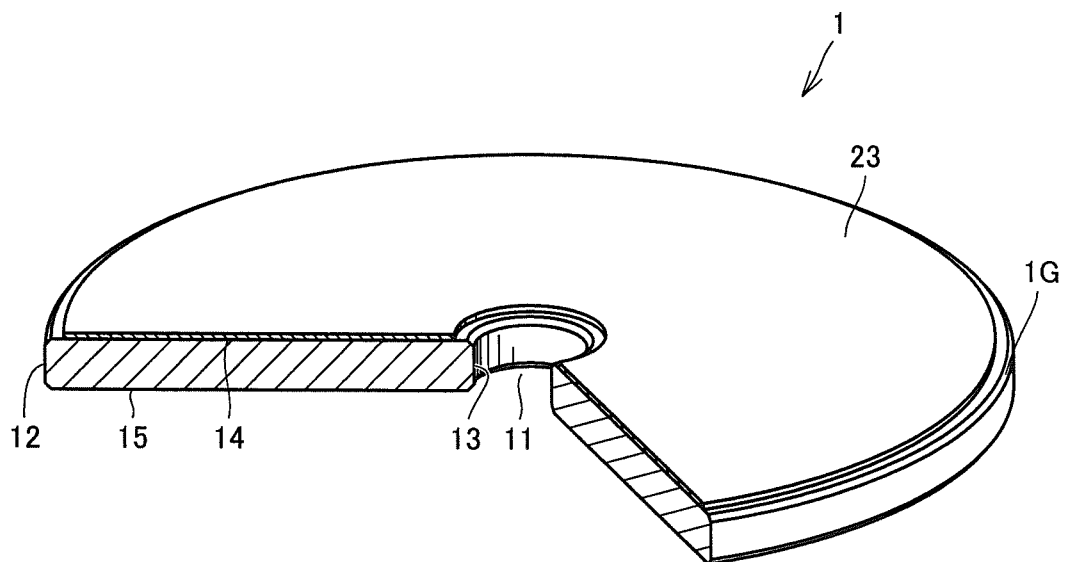


FIG.4

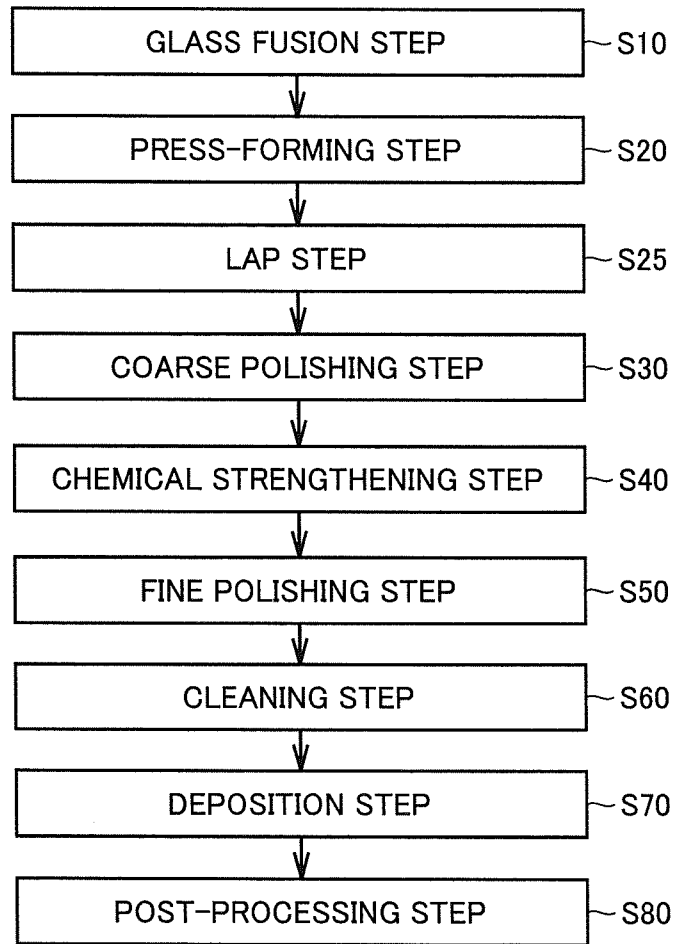


FIG.5

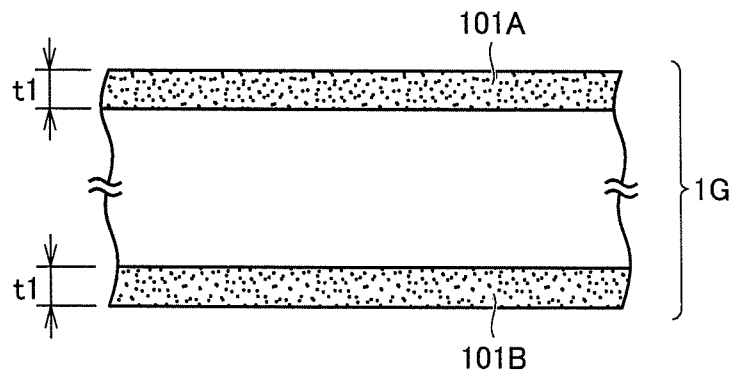


FIG. 6

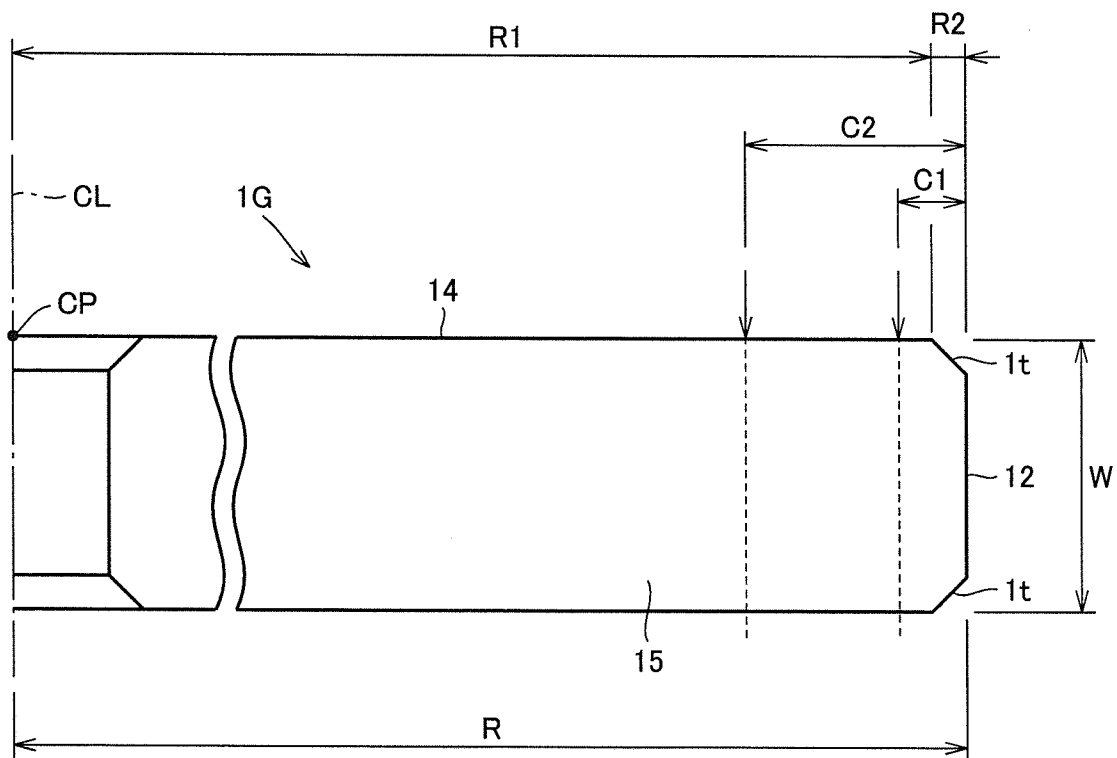


FIG. 7

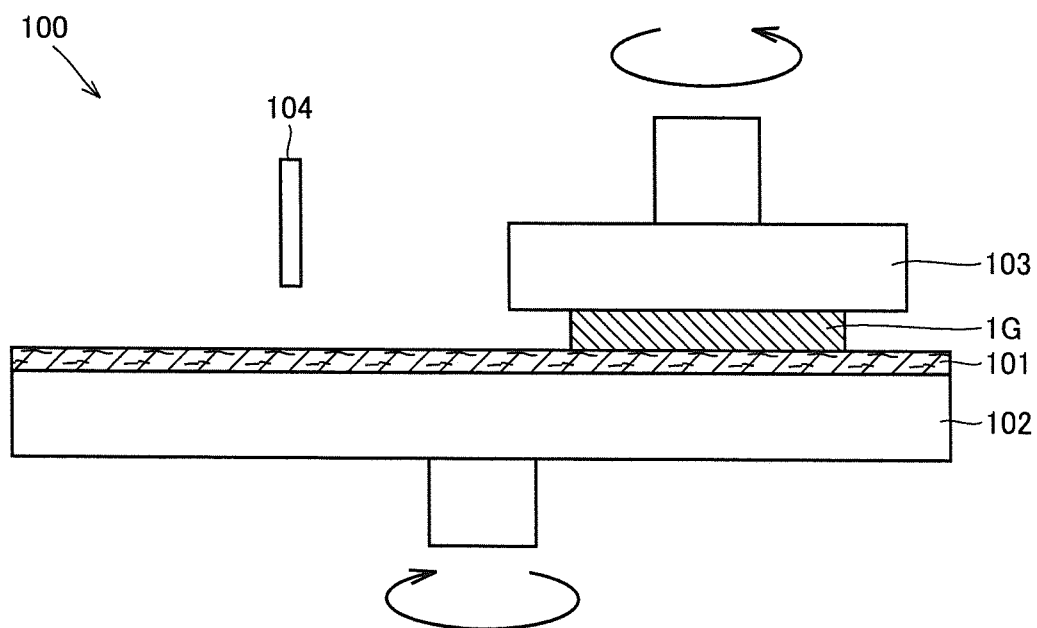


FIG.8

	FIRST POLISHING AMOUNT DIFFERENCE IN FIRST CIRCUMFERENTIAL REGION (P1) (μm)	SECOND POLISHING AMOUNT DIFFERENCE IN SECOND CIRCUMFERENTIAL REGION (P2) (μm)	FLOATING TEST (1) 6.5 mm FROM OUTER PERIPHERAL END SURFACE FLOATING HEIGHT 20 nm	FLOATING TEST (2) 6.5 mm FROM OUTER PERIPHERAL END SURFACE FLOATING HEIGHT 5 nm	FLOATING TEST (3) 2.5 mm FROM OUTER PERIPHERAL END SURFACE FLOATING HEIGHT 5 nm	NOTES
EXAMPLE 1	0.05	0.04	A	A	A	INNER/OUTER PERIPHERAL GOOD
COMPARATIVE EXAMPLE 1	0.12	0.08	A	A	B	INNER PERIPHERAL GOOD
COMPARATIVE EXAMPLE 2	0.17	0.09	A	A	C	OUTER PERIPHERAL NO GOOD
COMPARATIVE EXAMPLE 3	0.21	0.14	A	C	C	OUTER PERIPHERAL NO GOOD
COMPARATIVE EXAMPLE 4	0.35	0.25	C	C	C	INNER/OUTER PERIPHERAL NO GOOD

※ DIFFERENCE OF STOCK REMOVAL IS PRODUCED BY SINGLE-SIDE PROCESSING

※ A = PASS IN BOTH TESTS, B = PASS IN 25° C TEST/FAIL IN 70° C TEST, C = FAIL IN BOTH TESTS

FIG. 9

